

Manufacturing Process Variations and Dependability A Contrarian View

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Semiconductor Trends

- **Technology Projections from ITRS**

- 15 Years in to future
- CMOS will continue to dominate
- Some of the concerns of scaling
 - ◆ Manufacturing Defects
 - ◆ Age dependent degradation
 - ◆ Process Variations

Trends in Circuit Technology

- **Supply Voltage is Decreasing to save Power**
 - Reduces Signal to Noise Ratio
- **Device Threshold is Decreasing to maintain or increase performance**
 - Increases Sub-threshold Leakage Currents
- **Wires are getting taller and closer**
 - Increases Coupling Capacitance
 - Increases Crosstalk Noise
- **Statistical designs vs. Worst Case assumptions**
- **Manufacturing Test is getting harder**
 - Some timing defects go undetected

Manufacturing Defects

- **Defect Density**

- Number of Electrical Defects/m² chip area
- Defect Density has a direct impact on the Yield and hence the profitability of a manufacturing line
- Since testing for defects is an imperfect process, defect density also impacts quality
- ITRS goal for the next Five years is
 - ◆ Maintain defect density constant at 1395 defects/m²
- Since the number of transistors double every 2-3 years per unit area, the defects/transistor must halve every 2-3 years!!

➤ **Hard Faults: Not a serious concern for dependability**



Age Dependent Faults

- **Known Sources of Degradations**

- Gate oxide breakdown, Charge trapping in oxide, metal migration, structural weakening of dielectric and interconnect from thermal fluctuations
- These effects are accurately predictable from physical model and lab measurements
- ITRS projects
 - ◆ Short term goals: 50 to 2000 failed parts/million
 - ◆ Long term goals:
10 to 100 FITS (failures/billion device-hours)

➤ **Failures per/transistor must decrease!**



Process Variations

- **Sources of Variations**

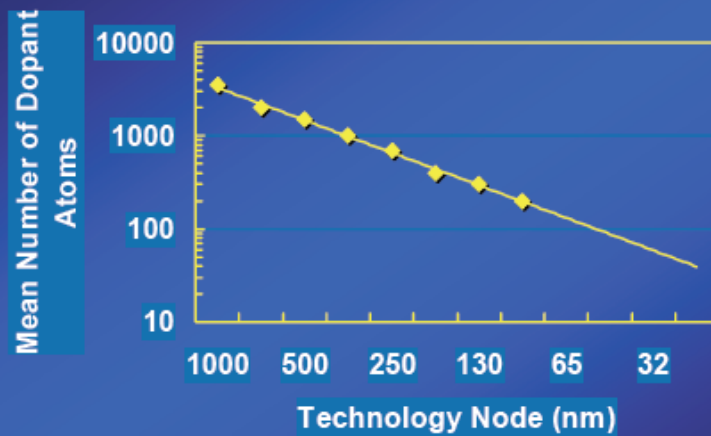
- Gate Oxide thickness
- Doping density
- Device geometry, Lithography in nanometer region
- Transistor Threshold V_T
 - ◆ Sub threshold current, leakage, power, frequency

- **Range of Variations**

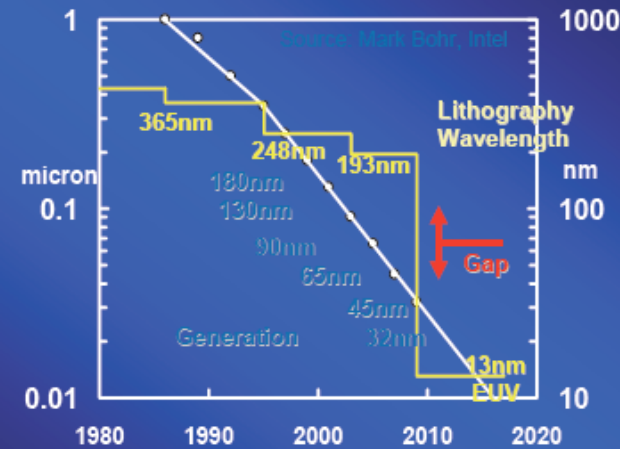
- 100% V_T variation across a modern chip
- 30% speed variation across a wafer
- 100% leakage (static power) variation in a wafer

Sources of Variations

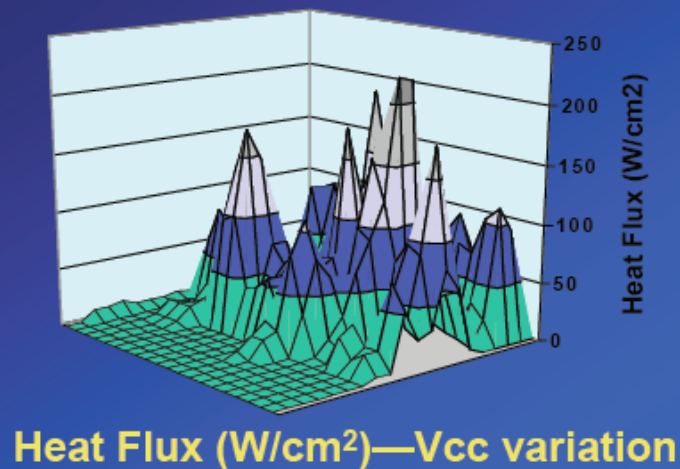
(from Shekhar Borkar, Intel)



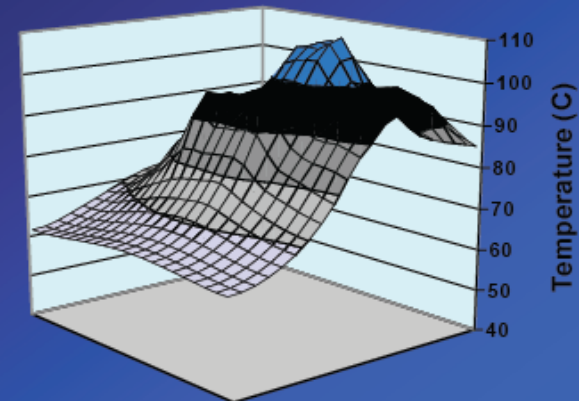
Random Dopant Fluctuations



Sub-wavelength Lithography

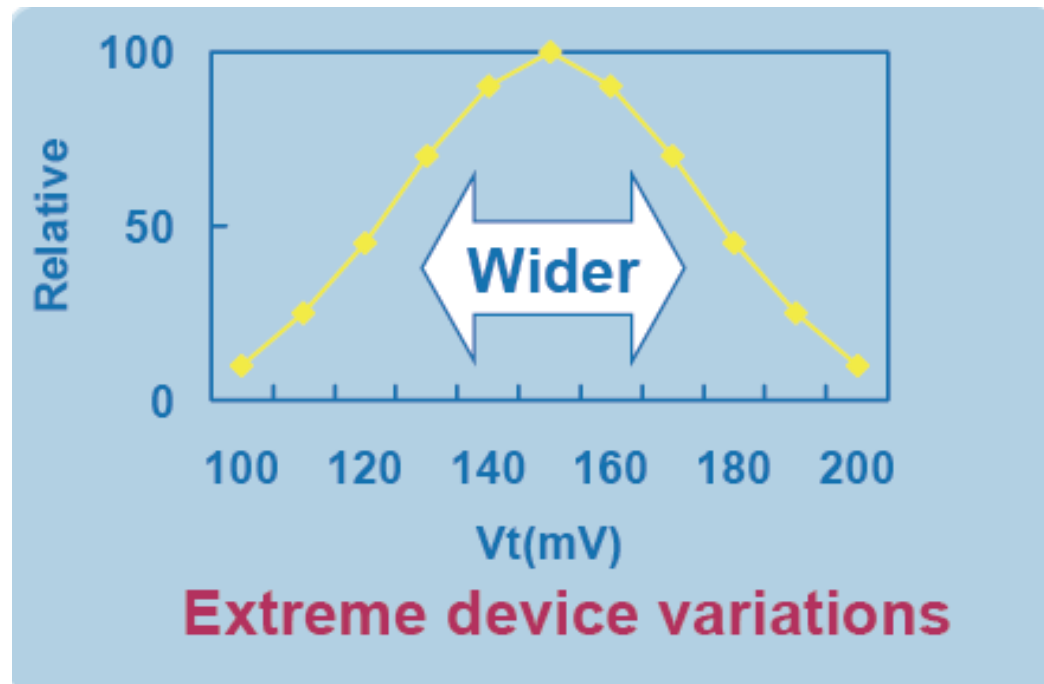


Heat Flux (W/cm²)—Vcc variation



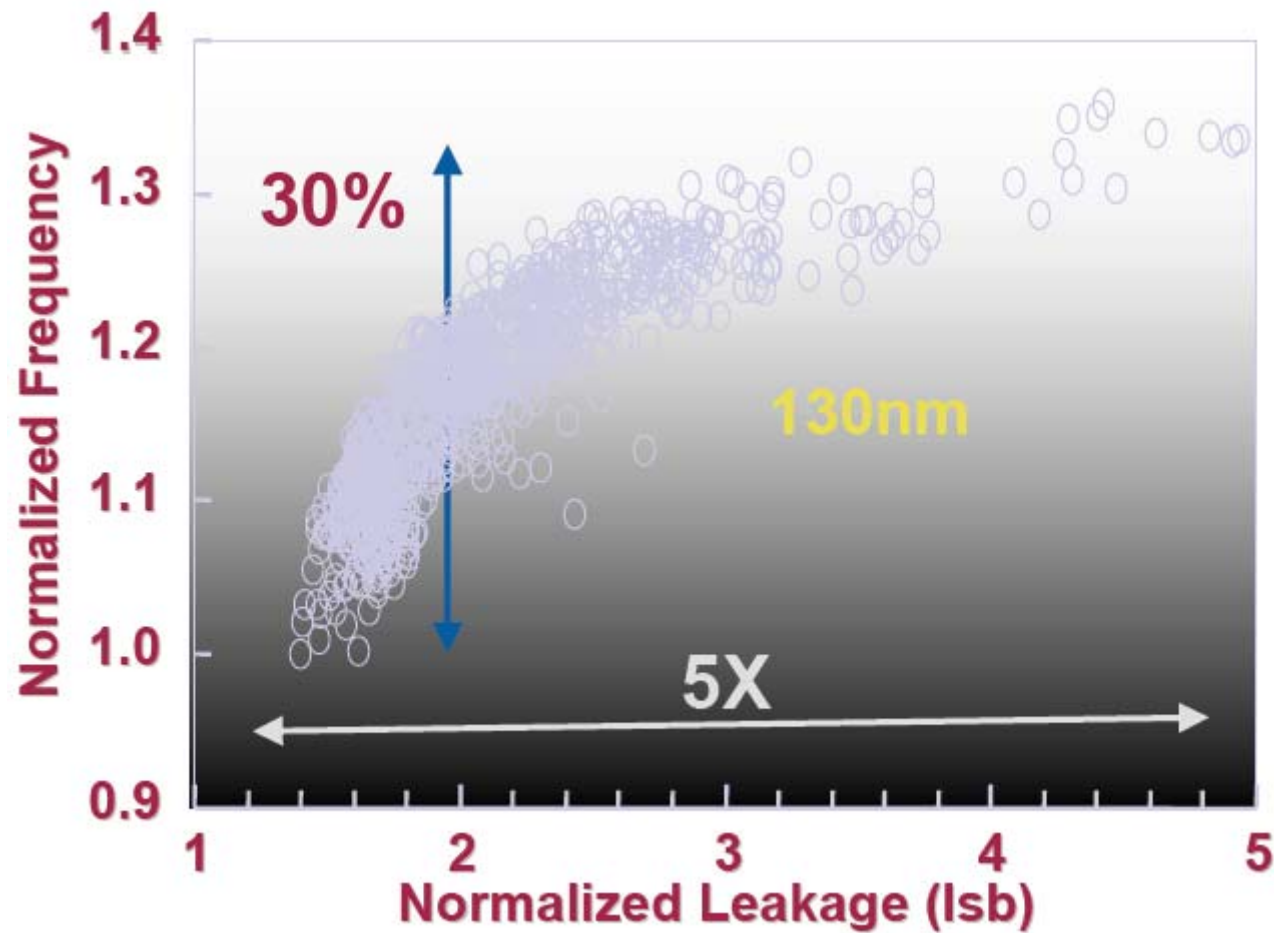
Temp Variation & Hot spots

Transistor Threshold V_t

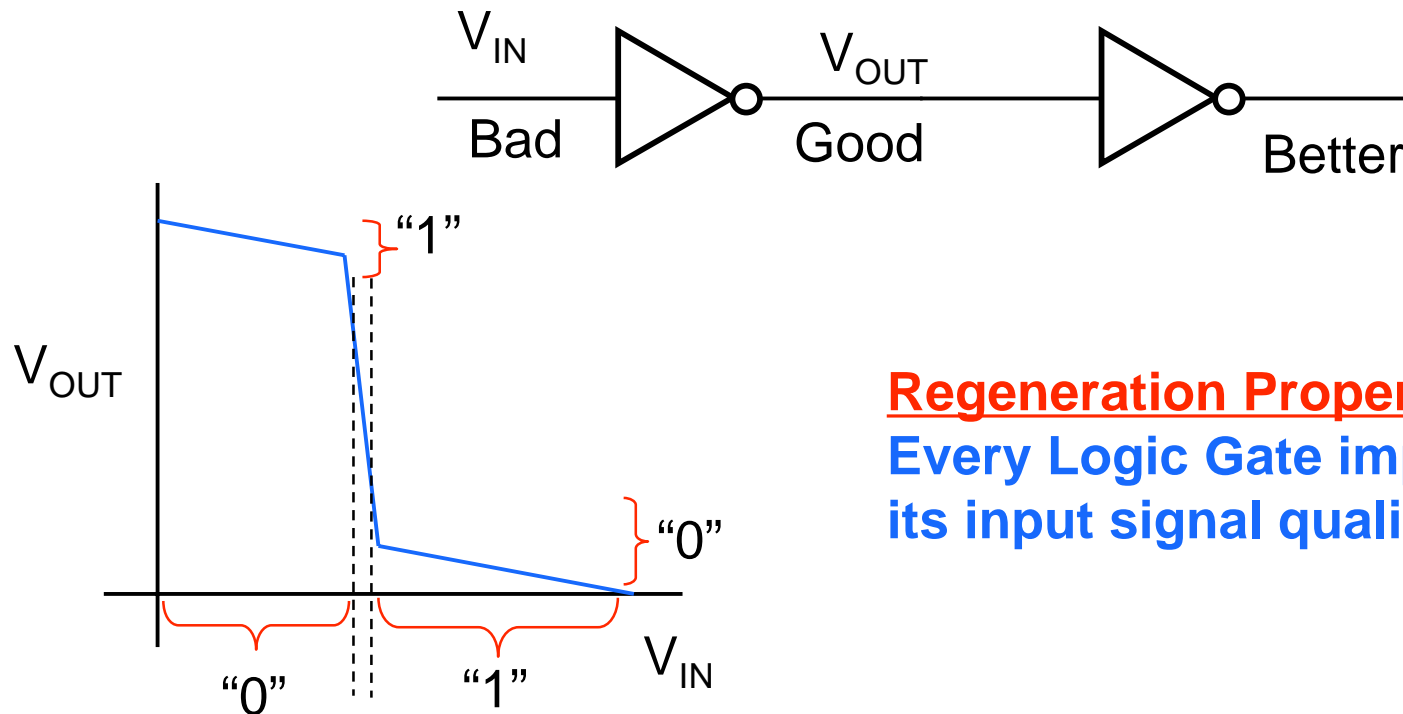


Static Variations today

(source: Shekhar Borkar, Intel)



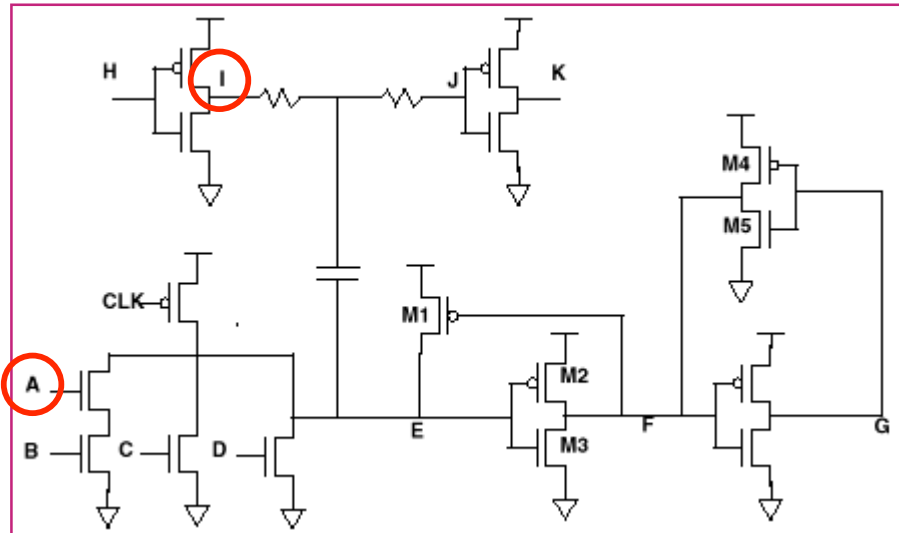
Inherent Robustness of Gates



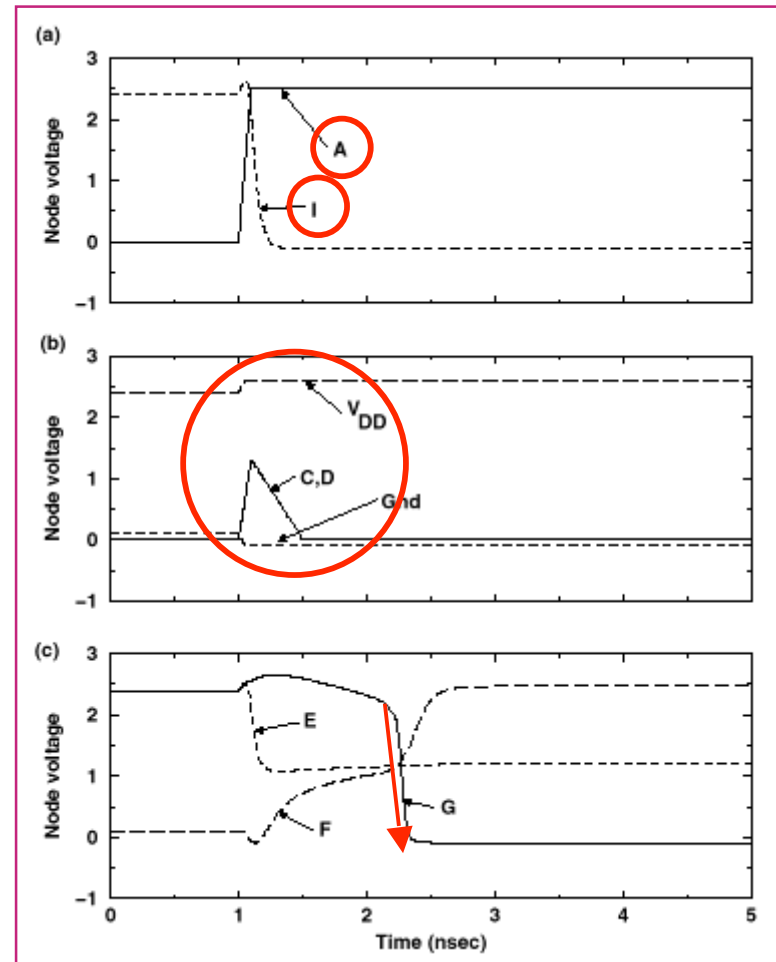
Regeneration Property:
Every Logic Gate improves
its input signal quality

Voltage Transfer Curve

Example: Circuit Simulation of A Bit Flip due to Noise



- (a) Driver output **I** is switching as is node **A**.
- (b) Coupling noise appears on inputs **C** and **D** along with power-supply noise on the voltage rails.
- (c) The dynamic node **E** falls, switching the output inverter of the domino gate **F** and the latch output **G**.

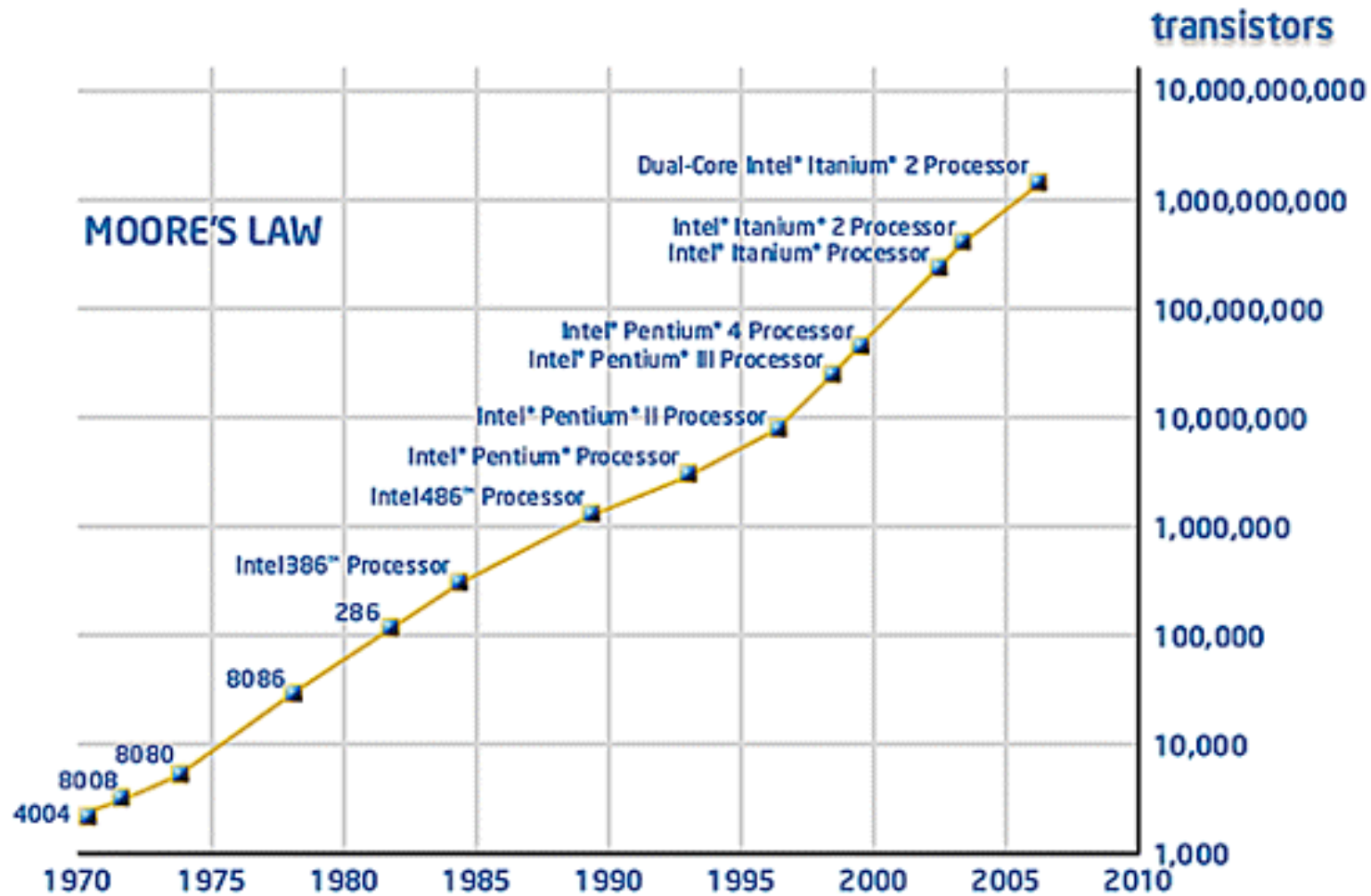


Source: Kenneth L. Shepard, "Design methodologies for noise in digital integrated circuits," 35th Design Automation Conf. pp. 94-99, 1998. © 1998 ACM

A Thought Experiment

- **Let us suppose process variations in future are so large as to have some transistors very slow**
 - Let us say 0.1% of all transistors are very slow
 - If we exercise the microprocessor with extremely large work load – lots of computations, lots of switching activity, large temperature variations, we should see some errors
 - 0.1% of one Billion Transistors is 1 Million!
 - 0.01% of one Billion is 100k
- **Hypothesis**
 - 100k slow transistors must cause massive failures!

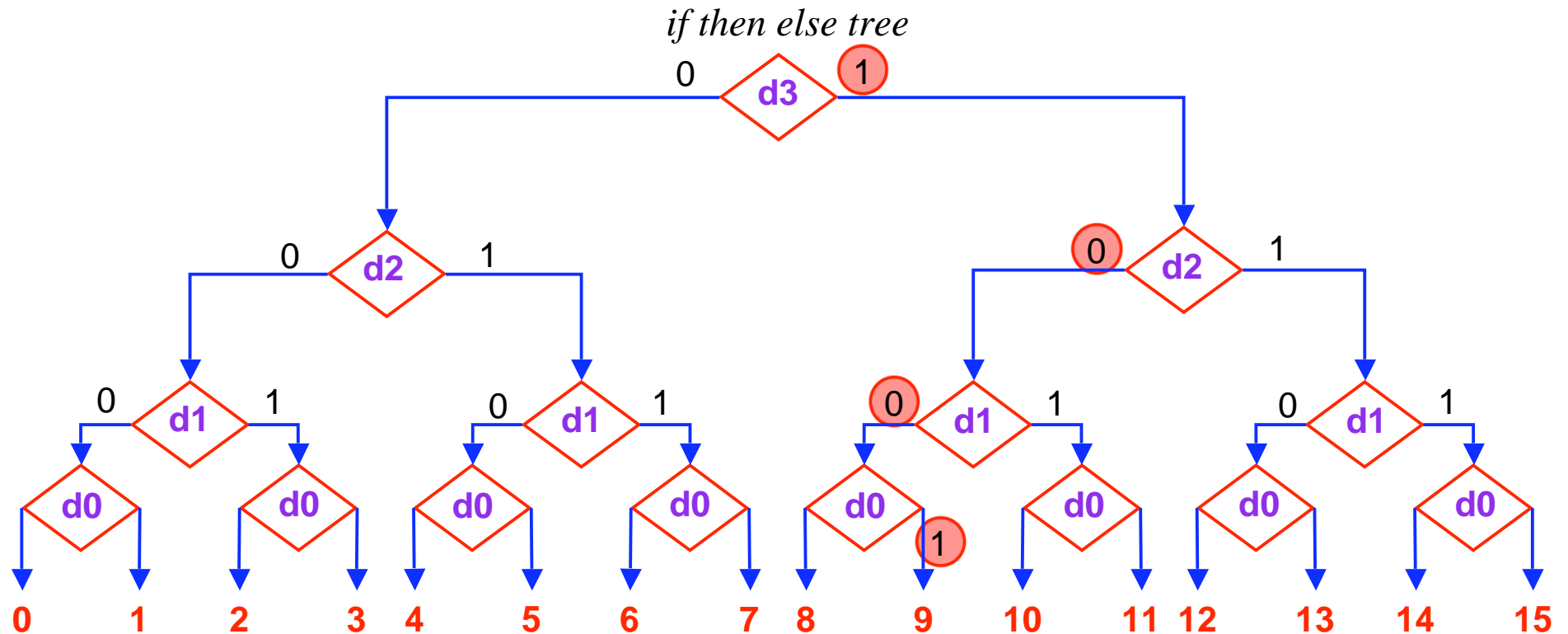
Moore's Law



Exercising a Microprocessor

- For each ALU Operation (e.g. ADD, SUB, AND, XOR, ...) several operations with known operands and known results are placed in a tight loop
- Try to **maximize the execution rate** of each operation
- Try to **maximize the logic switching** rate
 - High switching causes IR drop in power bus
- Try to utilize **all** functional units
- Exercise pipeline control logic
 - Independent and Dependent Operation

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Integer $d_3d_2d_1d_0 = 1001 = 9$

Experimentation with PowerPC 750

Routine	Operations per loop	Number of loops	Total Operations	Approx. Running Time	Approx. Operations Per Second
Register Unit	40	8,000,000	320,000,000	6.34 s	50.47x10⁶
Instruction Fetch Unit	32	8,000,000	256,000,000	92.04 s	2.78x10⁶
Integer Addition	40	8,000,000	320,000,000	9.35 s	34.22x10⁶
Integer Subtraction	40	8,000,000	320,000,000	9.12 s	35.09x10⁶
Integer Multiplication	58	8,000,000	464,000,000	18.21 s	25.48x10⁶
Integer Division	50	8,000,000	400,000,000	33.72 s	11.86x10⁶
Logical AND	20	8,000,000	160,000,000	0.71 s	225.35x10⁶
Logical OR	20	8,000,000	160,000,000	0.64 s	250.00x10⁶
Logical XOR	20	8,000,000	160,000,000	0.71 s	225.35x10⁶
Integer Unit 2	40 adds & multiplies	8,000,000	640,000,000	48.75 s	13.13x10⁶
Floating Point Add	20	8,000,000	160,000,000	0.82 s	195.12x10⁶
Floating Point Subtract	20	8,000,000	160,000,000	0.82 s	195.12x10⁶
Floating Point Multiply	20	8,000,000	160,000,000	0.83 s	192.77x10⁶
Floating Point Divide	20	8,000,000	160,000,000	0.82 s	195.12x10⁶
Branch Processing Unit	7	8,000,000	56,000,000	6.09 s	9.20x10⁶
Load/Store Unit	320 loads, 192 stores	80,000	40,960,000	13.24 s	3.09x10⁶
Data Cache	2	3,300,000	6,600,000	15.97 s	0.41x10⁶

Experimental Set-UP

- **A Single-Board-Computer (SBC)**
 - WindRiver SBC750
 - Motorola PowerPC 750 Microprocessor
 - 233MHz, 2.5V Power Supply
 - A Host Computer
 - WindRiver debugging software
 - HyperTerminal Software for serial communication
 - A Hewlett-Packard E3631A Power Supply
 - ◆ Digital control in units of $1/100^{\text{th}}$ Volt changes
 - A Blow-Drier to raise the temperature

Results of Lowering Supply Voltage

Board No.	No. Tests	Error Generated at Supply Voltage	Control Flow Errors Detected	
			System Hangs	Program Crashed
1	45	1.99 V – 2.10 V	31	14
2	35	2.00 V – 2.08 V	26	9
3	25	2.10 V – 2.29 V	18	7
4	25	2.08 V – 2.20 V	17	8

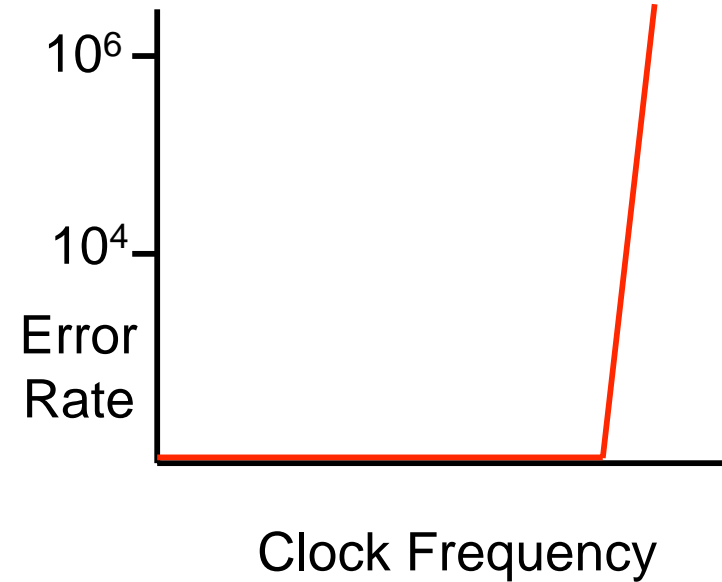
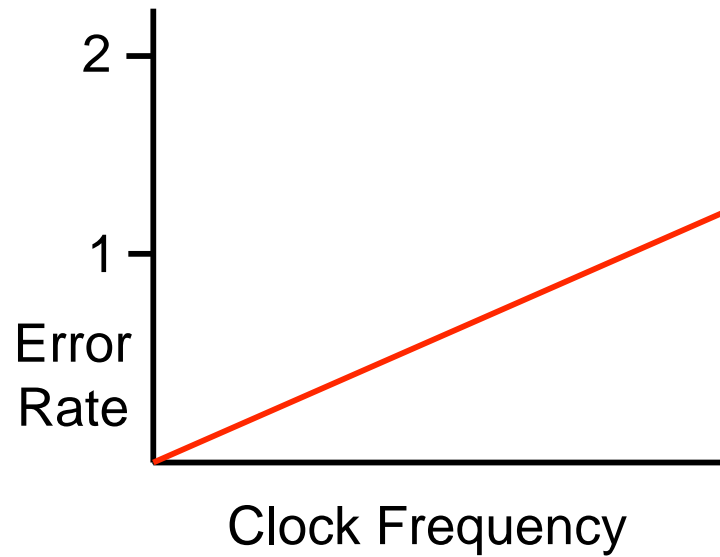
Nominal Supply Voltage of 2.5 V is reduced in steps of 1/100th Volt

No Data Error was ever Observed at user visible Registers!

Some Remarks on Experiment

- **Possible explanation for the crashes**
 - Control errors are always catastrophic
 - Most Critical Paths are in Control Logic
 - Control Logic fails before ALU datapath
- **Alternative explanation**
 - A large number of transistors affected simultaneously
 - An exponential number of logic paths affected
 - Massive failure in control and data

Outcome of Process Variations



Final Remarks

- **CMOS technology is robust now and will continue to be so for the future**
 - Process Variation related errors must be massive
 - No industry can survive with massive failures
 - Process variations must remain bounded
- **Where does dependability come in?**
 - Perhaps in yield improvement for multi-core microprocessors
 - Perhaps in relaxing design rules for cost and power reduction
 - Early Diagnosis for Yield Learning







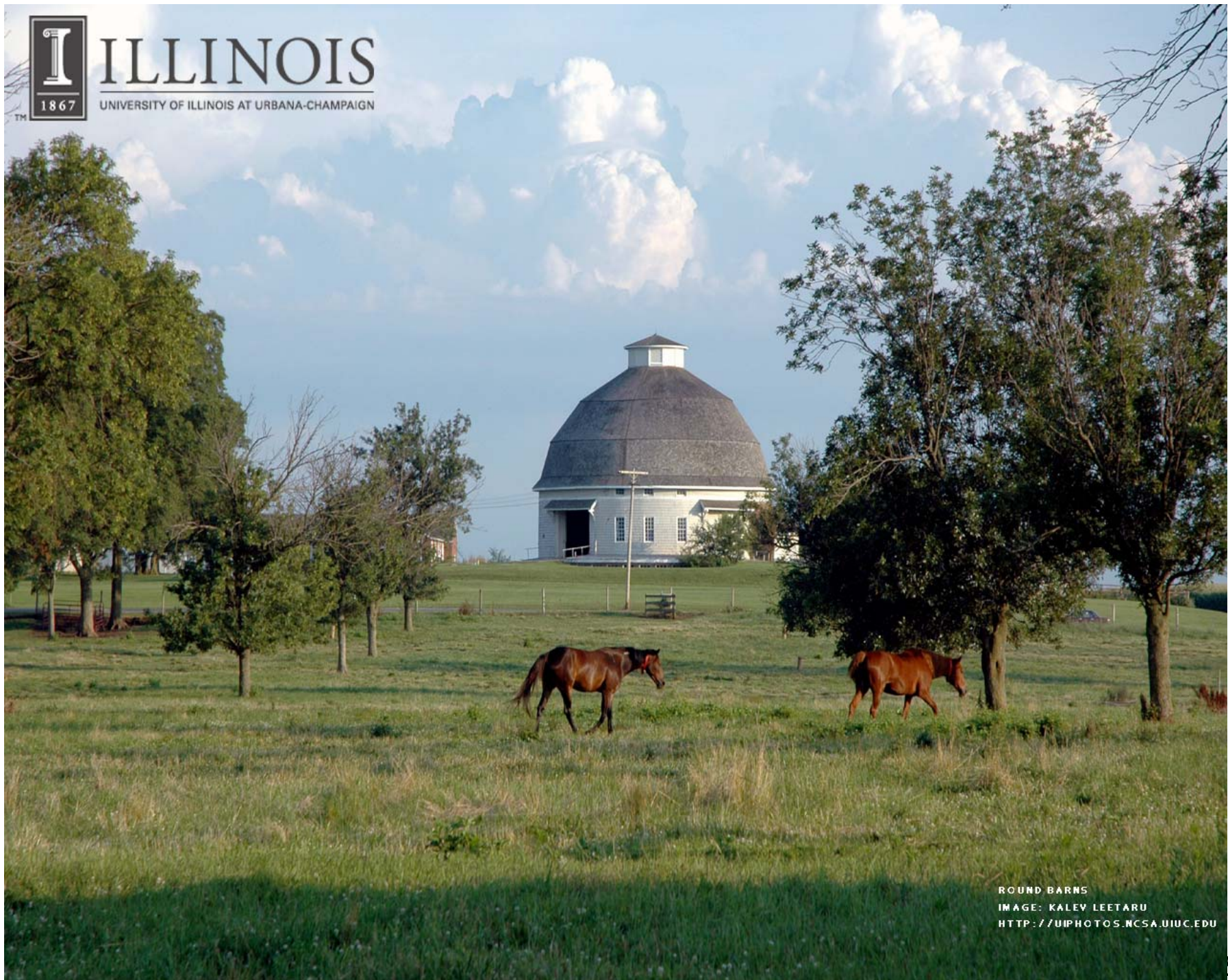






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ROUND BARN
IMAGE: KALEV LEETARU
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